PATENT
Atty. Dkt. No. AMAT/5908/CPI/ALUMINUM/PJS

IN THE CLAIMS:

Please cancel claims 1-54 without prejudice and amend the claims as follows:

1-54. (Canceled)

- 55. (Currently Amended) A semiconductor wafer processing system, comprising:
- a first chamber and a second chamber respectively enclosing a first robot and a second robot, the first and second chambers each having one or more processing chambers attached thereto;
- a load lock comprising a heating element and attached to the first chamber; and two or more transition chambers which separate the first and second chambers, the transition chambers each comprising a heating element disposed therein.
- 56. (Original) The semiconductor wafer processing system of claim 55, wherein the transition chamber heating element comprises a lamp.
- 57. (Original) The semiconductor wafer processing system of claim 56, wherein the transition chambers each comprise two wafer holders.
- 58. (Original) The semiconductor wafer processing system of claim 57, wherein the transition chambers each comprise a cooling plate.
- 59. (Original) The semiconductor wafer processing system of claim 55, wherein the transition chamber heating element comprises a resistive heater.
- 60. (Original) The semiconductor wafer processing system of claim 59, wherein the transition chambers each comprise a wafer holder.

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- 61. (Currently Amended) A semiconductor wafer processing system, comprising:
- a chamber <u>enclosing first and second robots and</u> having one or more processing chambers attached thereto:
- a load lock comprising a heating element, the load lock being attached to the chamber; and

two or more transition chambers within the chamber, each transition chamber comprising a heating element disposed therein.

- 62. (Original) The semiconductor wafer processing system of claim 61, wherein the transition chamber heating element comprises a lamp.
- 63. (Original) The semiconductor wafer processing system of claim 62, wherein the transition chambers each comprise two wafer holders.
- 64. (Original) The semiconductor wafer processing system of claim 63, wherein the transition chambers each comprise a cooling plate.